

(19)
(12)

(KR)
(A)

(51) 。 Int. Cl. ⁷
G02B 3/00

(11)
(43)

2002 - 0072659
2002 09 18

(21) 10 - 2001 - 0012605
(22) 2001 03 12

(71) 373 - 1

(72) 103 501

321 - 4 101

(74)
:

(54)

(reflow) (hyperhemisphere) ; 가
.
(lateral etching) ; 가
가 가 . ,

1f

, , , , , , , ,

1a 1f ;

2a 2b ;

3 (array) (line) ;

4 3 가 .

* *

10 :

20 :

20a :

30 :

30a :

30b :

30c :

40 :

50 :

60a :

60b :

re) , (reflow) (hyperhemisphe

가 가 가 . 가 가 (thermal reflow usin
g surface tension), (plastic molding with isotropic etch
ing of silicon), (selective ion exchange in a glass substrate)
가 (reflow) 가
(hemisphere) (hyperhemis

2a 2b 2a ,
 가 (20a) (30c) (hyperhemisphere) 가
 (hemisphere) 2b 가 (20a) (30c)

3 (array)
 , 3 , (60a)
 (60b)가 , 가

4 3 가 (optical fiber)

 가 ,
 가 가 가

(57)

1. ;
 가 ;
2. 가 ;
 가 .
3. 1 , 가
4. 1 , 가

1 ,

5.

1 ,

6.

1 , , 가

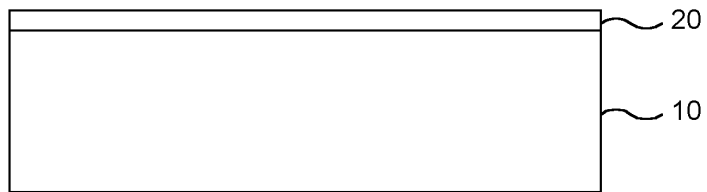
7.

1 , 가 가
180 ~ 300

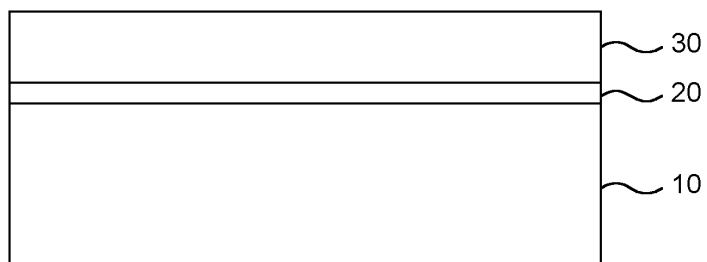
8.

1 7 가 , 2 2 ,

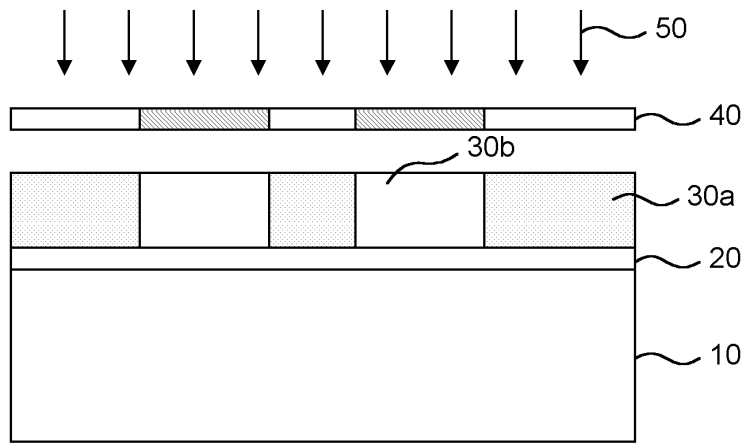
1a



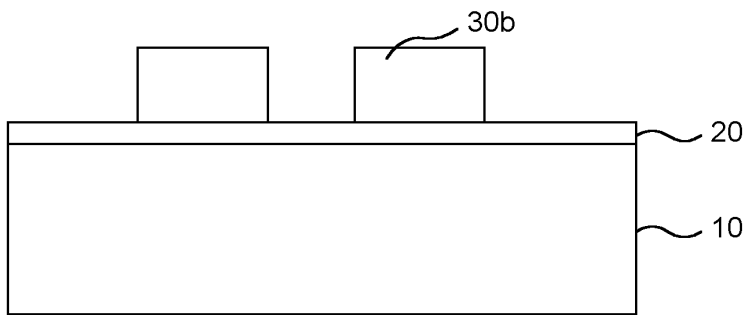
1b



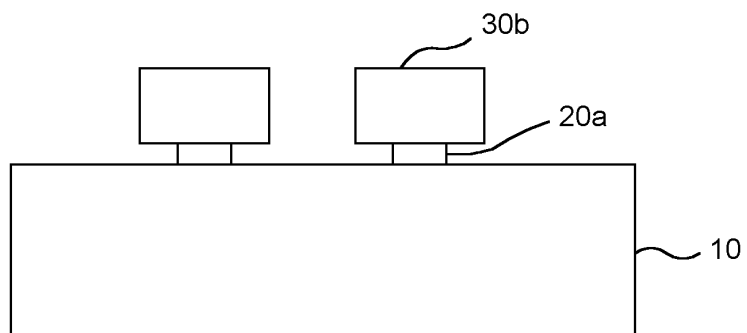
1c



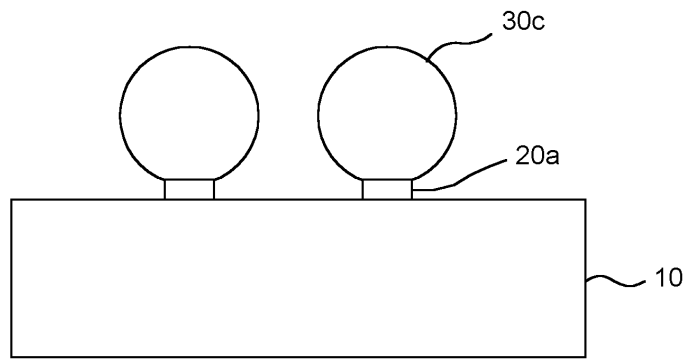
1d



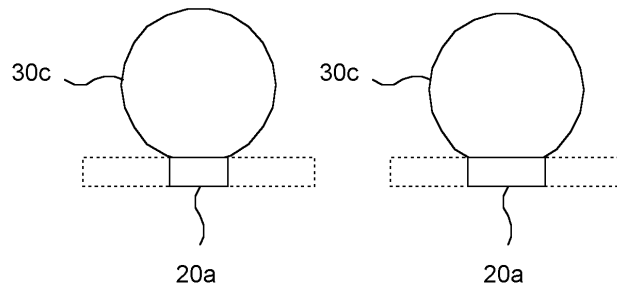
1e



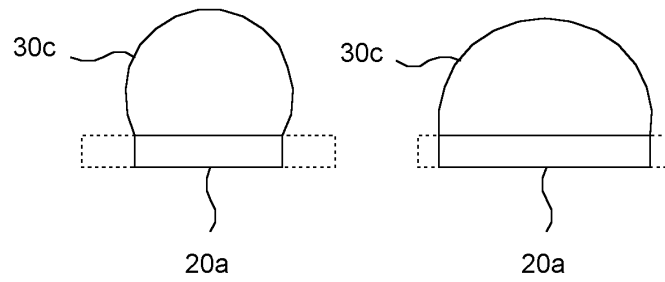
1f



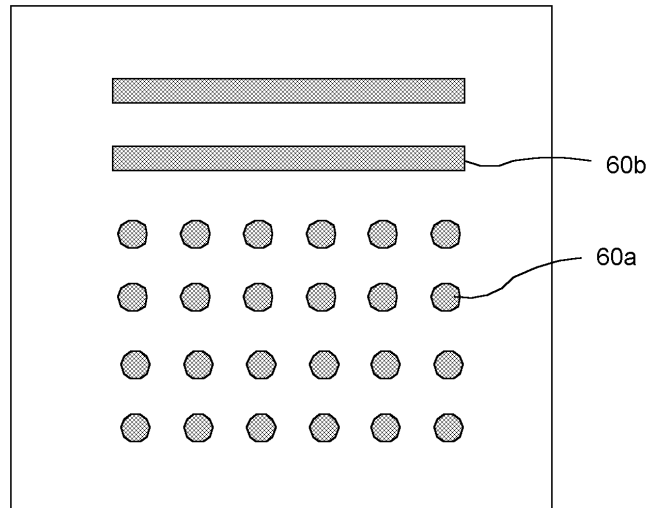
2a



2b



3



4

